

In the Specification

Paragraph 0018 on page 4 has been amended as follows:

Further advantageous refinements and developments of the invention emerge from the subclaims and from the exemplary embodiments described in principle below with reference to the drawing, in which:

figure 1 shows a basic representation of a faceted mirror according to the invention, arranged in an EUV lighting system for microlithography,

~~figure 2 shows a first method of production for a faceted mirror,~~

~~figure 2a shows a first method of production for a faceted mirror,~~

figure 2b shows a side sectional view of the faceted mirror of figure 2
~~2a taken along the line 2b-2b,~~

figure 3 shows a second method of production for a faceted mirror,
and

figure 4 shows a basic body for a faceted mirror with reinforcements in a honeycomb structure and with cooling channels.

Paragraph 0020 on page 5 has been amended as follows:

The production of the faceted mirror 1 with correspondingly high precision and homogeneous or as-desired illumination takes place according to figures ~~2a~~ 2 and 2b on a basic body 8. The basic body 8 may be formed for example by galvanic means, its functional surface corresponding with respect to curvature and position to the requirements which the finished faceted mirror 1 has to meet. Only the surface quality is still lacking. The surface quality is then realized by individual mirror elements 9 as optical elements.